



Docket: CS 99 - 065  
S/N: 09/442,499

1763

To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

From: George O. Saile, Reg. No. 19,572  
20 McIntosh Drive  
Poughkeepsie, N.Y. 12603

Subject:

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GROUP 1700

#16-1  
3/11/03  
m2

Serial No.: 09/442,499 Filed: 11/18/99  
Inventor: Ho

Title: Plasma Etch Method For Forming Plasma Etched Silicon  
Layer

Group Art Unit: 1763 Examiner: Goudreau, G. A.  
Attorney Docket: CS 99 - 065

#### RESPONSE TO PATENT OFFICE ACTION

Dear Sir:

In response to the office action dated 11/25/02, please consider the following remarks:

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patent and Trademarks, Washington, D.C. 20231, on February 25, 2003.

Signature/Date

  
Stephen B. Ackerman, Reg #37,761  
2/25/03